

The pH effects on the capacitive behavior of nanostructured molybdenum oxide

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Abstract Nanostructured molybdenum oxide having a particle size in the range of 30–80 nm was prepared by potentiodynamic electrodeposition method, and the effects of H₂SO₄ concentration on its capacitive behavior were studied by cyclic voltammetry, galvanostatic discharge, and electrochemical impedance spectroscopy. Poor to fair capacitive behaviors were witnessed depending on the electrolyte concentration and conditions of charge/discharge. Increasing acid concentration to 0.02 M had favorable effect, while beyond that, the effect was detrimental. Capacitance around 600 F g⁻¹ was recorded in the potential range of 0 to -0.55 V vs. Ag/AgCl.

Keywords Molybdenum oxides · Nanostructure · Impedance spectroscopy · Capacitive behavior

Introduction

Transition metal oxides are suitable materials to host small ions like H⁺ and Li⁺ in intercalation/deintercalation processes, which makes them most demanded for a wide range of applications such as electrochromic and energy storage devices. Among metal oxides, molybdenum oxide seems to be a promising candidate for such applications due to its crystallographic structure and different oxidation states of

molybdenum [1]. In fact, molybdenum oxide's interesting physical and chemical properties, including n-type semi-conductivity, electrochromism, and reversible small ions storage, make it a potential material for catalysts [2], gas sensors [3,4], smart windows [5], and batteries [6–8] applications.

Among different methods for preparing molybdenum oxides, electrodeposition technique sounds to be the most economic and suitable for making thin films due to its lower energy consumption and good sticking of the film to a conducting supports. There are several reports on the synthesis of molybdenum oxides by electrodeposition method [9–15]. Also, potentiodynamic electrodeposition method has been widely used for making nanostructured metal oxides [16–19]. The recent researches on the electrochemical properties of molybdenum oxide has shown that these properties depend not only to the nature of electrolyte but also to the morphology and the thickness of the oxide film, for instance, Więcek and Twardoch have reported a maximum capacitance of around 0.1 F cm⁻² for electrodeposited molybdenum oxides in 0.005 M H₂SO₄ [15], whereas Więcek and Kępas-Suwara have obtained a specific capacity of 160 F g⁻¹ in 0.1 M K₂SO₄ solution [20] and Takasu et al. a comparable capacitance to RuO₂ of around 1,000 F g⁻¹ at low loading amount (0.5 nmol cm⁻²) of highly dispersed and nanosized molybdenum oxides [21].

In this study, we prepared nanostructured molybdenum oxide by potentiodynamic electrodeposition onto stainless steel and investigated the effects of pH on its capacitive behavior by cyclic voltammetry, galvanic charge/discharge, and impedance spectroscopy. Also, we studied the limitation in acid concentration by monitoring instabilities of molybdenum oxides and side reactions like hydrogen evolution reaction.

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Experimental

The preparation method of nanostructured molybdenum oxide has been reported in details elsewhere [22]. Briefly, the amorphous nanostructured molybdenum oxide was potentiodynamically electrodeposited onto the surface of commercial grade stainless steel, which had been polished with emery paper nos. 400 to 1200 to a rough finish, washed free of emery particles in dilute nitric acid solution, rinsed with water, and air-dried. Electrodeposition was carried out in a (0.01 M H₂SO₄ + 0.04 M Na₂MoO₄) solution in the potential range of 0.00 to -0.75 V vs. Ag/AgCl with the potential sweep rate of 300 mV s⁻¹. H₂SO₄ and Na₂MoO₄ were Merck products, and all solutions were prepared using double distilled water. Subsequent to deposition, the obtained electrode was washed in distilled water and then used in electrochemical test solution, which hereafter we will call it as-deposited nanostructured molybdenum oxide, ANMO.

Electrochemical studies were carried out in a conventional three-electrode cell where the (coated) stainless steel sheet, a platinum grid, and a saturated Ag/AgCl electrode were used as a working, counter, and reference electrodes, respectively.

Cyclic voltammetry and galvanic charge/discharge tests were performed by a Solartron Electrochemical interface SI1287. Electrochemical impedance spectroscopy studies were carried out by a Solartron Phase Gain Analyzer SI1260. The electrochemical tests were performed in solutions of 0.005, 0.010, and 0.020 M H₂SO₄ at room temperature, and for each solution, a fresh working electrode was employed.

The amount of molybdenum oxides in the film was measured by dissolving of the film in a solution of nitric acid and analysis by ICP-OES (Varian, Australia), and the results were reported in terms of MoO₃. It was found that on average, 0.1 mg of MoO₃ exist on every square centimeter geometric area of the electrodes.

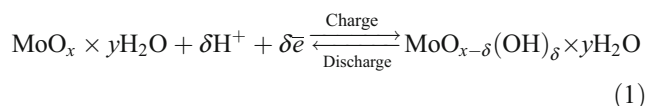
Measurements by scanning potential microscopy (Dual Scope SPM, DME, Denmark) revealed round particles of molybdenum oxides of between 30 and 80 nm diameters.

Results and discussion

Cyclic voltammetry studies

Figure 1 presents cyclic voltammograms (CV) of ANMO/H₂SO₄ system for various concentrations of sulfuric acid and recorded at different potential sweep rates. The potential window is properly selected not to render ANMO unstable. Figure 2 compares the CVs recorded at the same potential sweep rate in different sulfuric acid solutions.

Relatively poor capacitive behavior at high potential sweep rate and low acid concentration approaches to a fair, partially rectangular CV, as potential is swept slowly in higher acid concentrations. In fact, both the ionic charge transfer on the solution-electrode interface as well as the resistance related to the hydrogen inside the film should account for the kinetic limitation responsible for the deviation of the CVs from capacitive behavior [23]. Extending the cathodic end of the half-cycles tends to destroy the capacitive surface while hydrogen evolution accompanies. The redox processes responsible for the accumulation of charge is likely to be



while double-layer charging and diffusion of hydrogen ion (or else) from the surface to the interior of the active material (ANMO) certainly accompany reaction 1. This reaction resembling the origin of ruthenium oxide Faradaic capacitance [24] is in qualitative agreement with the CV findings. High acid concentration enhances charge accumulation but on the other hand favors instability and hydrogen evolution at less negative potentials.

Galvanostatic discharge curves

The capacitive behavior of a material can be estimated from charge/discharge follow:

$$\text{SC}(\text{F g}^{-1}) = \frac{i(\text{A}) \times \Delta t(\text{s})}{\Delta E(\text{V}) \times m(\text{g})} \quad (2)$$

where i is the current, Δt is the discharge time, ΔE is the change in potential during the discharge process, and m is the mass of the active material. Figure 3 presents the discharge curves of the as-deposited molybdenum oxide between -0.2 and -0.45 V vs. Ag/AgCl at 0.1 mA cm⁻² for different concentrations of H₂SO₄. Increasing the concentration of H₂SO₄, discharge time increases, which is related to more accumulated charge on the ANMO surface on the basis of the cyclic voltammetry results. Also, a sharp potential change is observed at initial stages of discharge, which is likely due to both IR drop and kinetic overpotential [25–27]. The assignments seem justified as upon increasing the acid concentration, the potential change diminishes on account of the increased conductivity of solution and more availability of protons for the Faradaic process. On the other hand, when the Faradaic process Eq. 1 cannot provide the required charge to be withdrawn at the particular cell current, a kinetic resistance builds up.

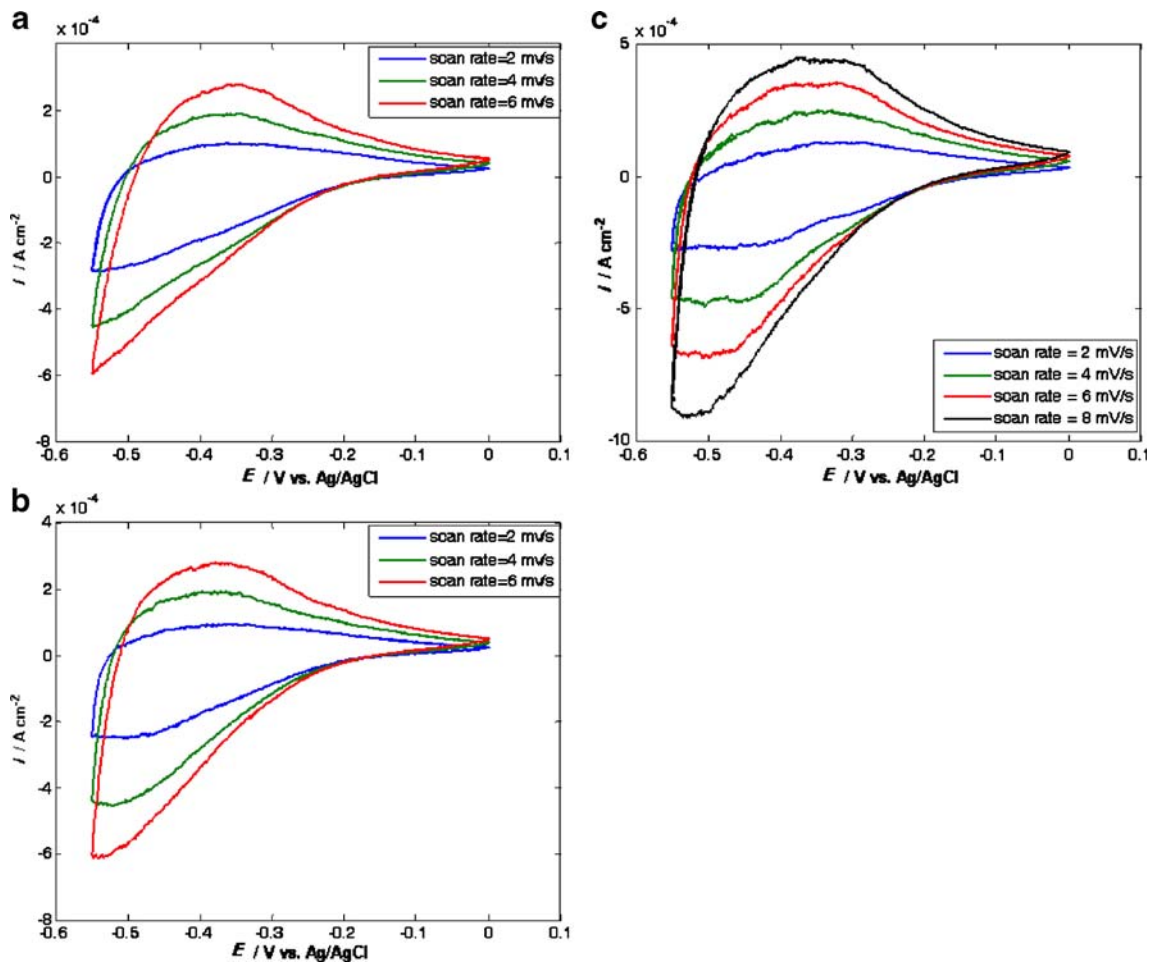


Fig. 1 Cyclic voltammograms of ANMO at different scan rates in **a** 0.005 M, **b** 0.010 M, and **c** 0.02 M H₂SO₄ solution

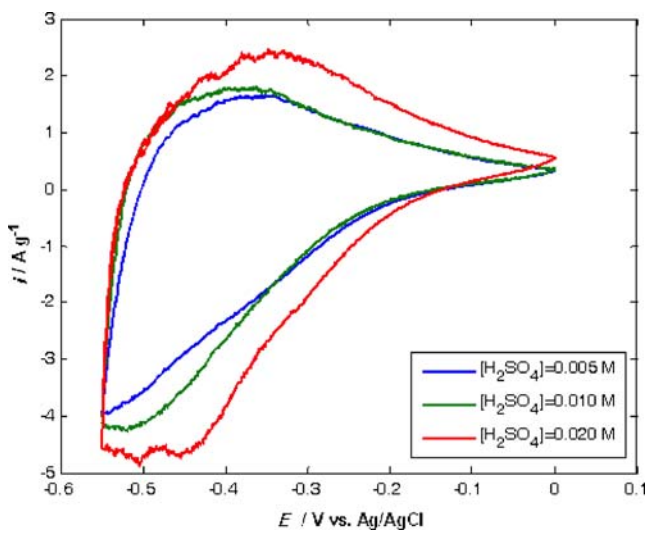


Fig. 2 Cyclic voltammograms of ANMO at scan rate of 4 mV/s in different concentrations of H₂SO₄

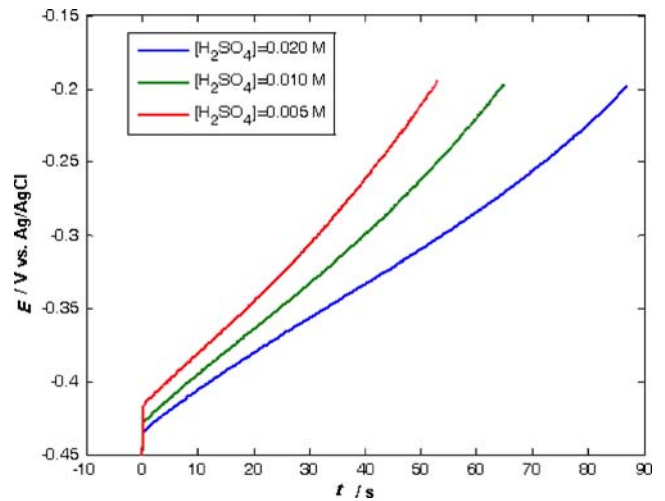


Fig. 3 Discharging curves of ANMO at 0.1 mA/cm² in different concentrations of H₂SO₄

Table 1 The discharge specific capacitance of ANMO at 0.1 mA/cm² cell current and different concentrations of H₂SO₄

[H ₂ SO ₄]/M	Specific capacitance/F g ⁻¹
0.005	347.4
0.010	467.0
0.020	650.1

The amount of the kinetic resistance is an evidence for disability of Faradaic process to supply charge at the required rate. In higher concentration of H₂SO₄, more hydrogen ions are available as a reagent for Faradaic reaction, and with regard to cyclic voltammetric studies, more accumulated charge exists to be withdrawn at the cell current and kinetic resistance thus decreases.

As Fig. 3 shows, the potential changes during discharging have two parts, a linear sharp change region and a mild nonlinear potential drop region [28], which runs the capacity of active electrodic materials. Due to this nonlinear

change in potential vs. time, ΔE in Eq. 2 should be considered as an average potential for second region [25–27], which is calculated by:

$$\Delta E_{ave} = \frac{1}{\Delta t} \int_{t_1}^{t_2} E dt \quad (3)$$

Specific discharge capacitances have been calculated by using galvanic discharging curves (Fig. 3), and Eqs. 2 and 3 and have been shown in Table 1. As these data show, discharging capacitance enhances by increasing in concentration of H₂SO₄, which satisfies the cyclic voltammetric results.

Electrochemical impedance spectroscopy studies

The complex-plane impedance (Nyquist plots) and dependency of impedance magnitude, phase angle, and capacitance on frequency (Bode plots) for ANMO -0.35 V vs. Ag/AgCl in different concentration of H₂SO₄ have been presented in Fig. 4a–d. The capacitance was calculated from the

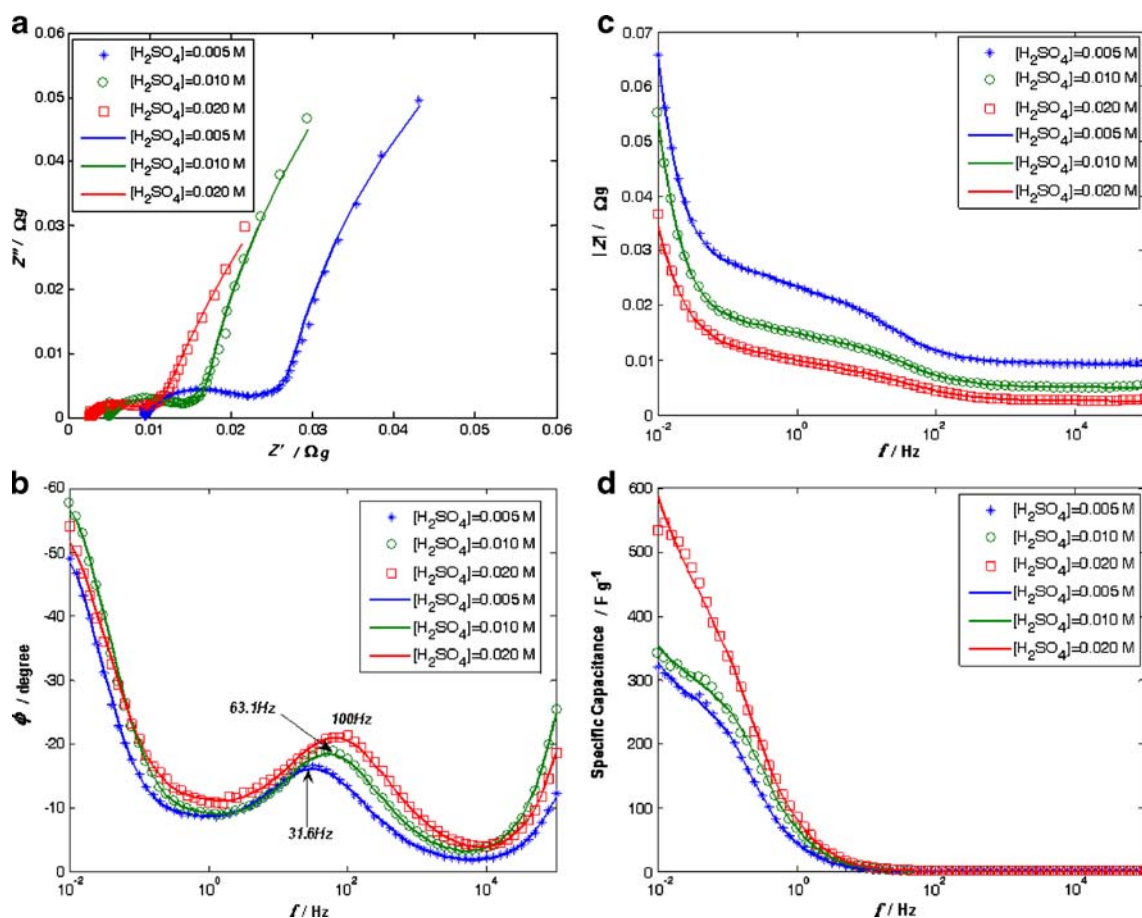


Fig. 4 The **a** Nyquist plots of ANMO in different concentrations of H₂SO₄ at -0.35 V vs. Ag/AgCl. Frequency dependence of the **b** phase angle; the characteristic knee frequency has been shown: **c** impedance

magnitude and **d** capacitance. The *solid lines* represent the fitted data to the equivalent circuit in Fig. 5

Table 2 The capacity of ANMO at different concentration of H₂SO₄ at -0.35 V vs. Ag/AgCl

[H ₂ SO ₄]/M	Specific capacitance/F g ⁻¹
0.005	315
0.010	365
0.020	580

frequency dependency of the imaginary part of the impedance, Z'', through:

$$C = \frac{1}{2\pi f Z''} \tag{4}$$

The Nyquist plots (Fig. 4a) exhibit a squashed semicircle terminating to a line (slightly curved) with a slope close to 90°. The existing deviations from the straight line are related to nonideality of the capacitor (leaking capacitor). The knee frequency values have been shown in Fig. 4b. The knee frequency is the lower limit of the high frequency region of impedance spectrum, a region where |Z| is weakly dependent on frequency (Fig. 4c) and the capacitance is near zero (Fig. 4d) [29]. At frequencies higher than the knee frequency, fast charge transfer processes, double-layer charging, etc. will dominate and slow Faradaic charge/discharge and mass transfer processes are thus ignored. The low frequency region is defined as the region where the Z-f plot possesses a slope close to -1 and -90° < φ < -45° in the f-φ plot. The near -1 slope shows that this region is typical of capacitive behavior. The frequency where φ = -45° is recognized as the frequency response to the ideal capacitor. At low frequency region (f ≤ f_{φ=-45°}), nonhomogeneous diffusion in the less accessible sites or leakage current may govern the impedance [29]. The range of frequencies between knee frequency and capacitor response frequency defines the medium frequency region where the kinetics of system is under diffusion control and distributed capacitance and resistance within the film (Warburg impedance) dominate the impedance. As Fig. 4b shows, by going to more concentrated solutions, the knee frequency increases. It means that double-layer charging occurs faster, or double-layer charging time constant becomes smaller. In

fact, at a higher concentration of acid and at a fixed potential, more hydrogen ions are available to make the interface charged. On the other hand, double-layer charging time constant inversely depends to the conductivities of solution and the solid matrix [25], and both of these conductivities increase by increasing in concentration of acid. The argument is in accord with results of f - |Z| plots (Fig. 4c). The argument is further supported by the diminished first semicircle and its shift to the lower limit of the real axis of the Nyquist plots. Also, by increasing in acid concentration, the semicircles become smaller more squashed, which imply that the double-layer capacitance increases, charge transfer resistance decreases, and more internal areas of the electrode is accessible. The phase angle behavior plots (Fig. 4b) show that the capacitor response frequency increases by increasing in concentration of acid, i.e. at higher concentrations, pseudo-capacitance is observed over a wider range of frequencies (Fig. 4d). Maximum capacitances, which are measured by impedance technique at -0.35 V vs. Ag/AgCl, have been collected in Table 2 for different solutions.

Finally, to have a better understanding of the parameters, which are important in impedance response of ANMO, we used the equivalent circuit shown in Fig. 5. This equivalent circuit has previously been employed by Sugimoto et al. [29] to investigate the response of hydrated ruthenium oxide in 10 M H₂SO₄.

The total impedance of equivalent circuit (Fig. 5) can be written as:

$$Z_{total} = R_s + \frac{1}{\frac{1}{Z_C} + \frac{1}{R_1 + Z_W} + \frac{1}{R_2 + \frac{1}{\frac{1}{R_3} + \frac{1}{Z_{CPE}}}}} \tag{5}$$

Where R_s is the solution resistance, Z_C is the double-layer impedance, and R₁ is the ohmic resistance accompanying mass transfer impedance, Z_W. R₂ is the charge transfer resistance through which pseudo-capacitance is charged/discharged, Z_{CPE} is the constant phase element signifying Faradic capacitance, and R₃ is the leakage resistance of the capacitor. This equivalent circuit fitted with the experimental data very well (solid lines in Fig. 4a–d), and some of the circuit parameters have been presented in Table 3.

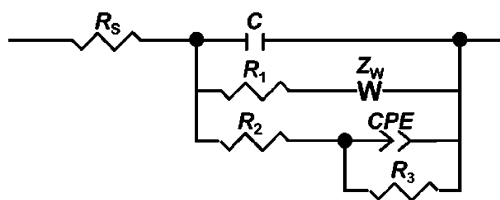


Fig. 5 The equivalent circuit used for fitting experimental results containing three parallel branches for double-layer capacitance, Warburg impedance, and a constant phase element signifying pseudo-capacitance

Table 3 Values of some of the equivalent circuit parameters at -0.35 V vs. Ag/AgCl in different concentrations of H₂SO₄

[H ₂ SO ₄]/M	C _{dl} /μFg ⁻¹	R _W /Ω g	R _{CT} /Ω g
0.005	646	0.0179	0.0191
0.010	573	0.0111	0.0151
0.020	929	0.0100	0.0091

Conclusion

The as-deposited nanostructured molybdenum oxide (ANMO) on stainless steel in acid solution shows capacitive behavior, which is enhanced by increasing the acid concentration. The leaky nature of the capacitor clearly appears in the Nyquist plots in the form of slightly curved capacitive lines. The instability of molybdenum oxide in acid solution acts as a limiting factor, which does not permit using high concentration of acid (>0.02 M) to achieve higher capacitances. Capacitance as high as 600 F g^{-1} has been measured.

References

- Bailar JC, Emel us HJ, Nyholm SR, Trotman-Dickenson AF (eds) (1973) *Comprehensive inorganic chemistry* vol 3. Pergamon, Oxford
- Heracleous E, Lee AF, Vasalos IA, Lemonidou AA (2003) *Catal Lett* 88:47. doi:10.1023/A:1023534816277
- Ferroni M, Guidi V, Martinelli G, Sacerdoti M, Nelli P, Sberveglieri G (1998) *Sens Actuator B* 48:285. doi:10.1016/S0925-4005(98) 00057-4
- Imawan C, Steffes H, Solzbacher F, Obermeier E (2001) *Sens Actuator B* 77:346. doi:10.1016/S0925-4005(01) 00732-8
- Granqvist CG (1995) *Handbook of inorganic electrochromic materials*. Elsevier, Amsterdam
- Shembel E, Apostolova R, Nagirny V, Kirsanova I, Grebenkin P, Lytvyn P (2005) *J Solid State Electrochem* 9:96. doi:10.1007/s10008-004-0565-2
- Yebka B, Julien C, Nazri GA (1999) *Ionics* 5:236. doi:10.1007/BF02375846
- Christian PA, Carides JN, DiSalvo FJ, Waszczak V (1980) *J Electrochem Soc* 127:2315. doi:10.1149/1.2129404
- McEvoy TM, Stevenson KJ (2003) *Anal Chim Acta* 496:39. doi:10.1016/j.aca.2002.10.001
- McEvoy TM, Stevenson KJ (2004) *J Mater Res* 19:429. doi:10.1557/jmr.2004.19.2.429
- McEvoy TM, Stevenson KJ, Hupp JT, Dang X (2003) *Langmuir* 19:4316. doi:10.1021/la027020u
- Pathan HM, Min SK, Jung KD, Joo OS (2006) *Electrochem Commun* 8:273. doi:10.1016/j.elecom.2005.11.022
- Guerfi A, Dao LH (1989) *J Electrochem Soc* 136:2435. doi:10.1149/1.2097408
- Nagirny VM, Apostolova RD, Baskevich AS, Shembel EM (2004) *Russ J Appl Chem* 77:71. doi:10.1023/B:RJAC.0000024579.88110.c3
- Wi ecek B, Twardoch U (2004) *J Phys Chem Solids* 65:263. doi:10.1016/j.jpcs.2003.08.022
- Prasad KR, Koga K, Miura N (2004) *Chem Mater* 16:1845. doi:10.1021/cm0497576
- Prasad KR, Miura N (2004) *J Power Sources* 135:354. doi:10.1016/j.jpowsour.2004.04.005
- Prasad KR, Miura N (2004) *Electrochem Commun* 6:1004. doi:10.1016/j.elecom.2004.07.017
- Prasad KR, Miura N (2004) *Electrochem Commun* 6:849. doi:10.1016/j.elecom.2004.06.009
- Wi ecek B, Kepas-Suwarana A (2007) *Pol J Chem* 81:129
- Takasu Y, Ohnuma T, Sugimoto W, Murakami Y (1999) *Electrochemistry* 67:1187
- Farsi H, Gobal F, Raissi H, Moghiminia S (2009) On the pseudocapacitive behavior of nanostructured molybdenum oxide. *J Solid State Electrochem*. doi:10.1007/s10008-009-830-5
- Garc a-Ca adas J, Mora-Ser o I, Fabregat-Santiago F, Bisquert J, Garc a-Belmonte G (2004) *J Electroanal Chem* 565:329. doi:10.1016/j.jelechem.2003.10.027
- Conway BE (1999) *Electrochemical supercapacitors: scientific fundamentals and technological applications*. Kluwer Academic/Plenum, New York
- Lin C, Ritter JA, Popov BN, White RE (1999) *J Electrochem Soc* 146:3168. doi:10.1149/1.1392450
- Farsi H, Gobal F (2007) *J Solid State Electrochem* 11:1085. doi:10.1007/s10008-006-0242-8
- Farsi H, Gobal F (2009) *J Solid State Electrochem* 13:433. doi:10.1007/s10008-008-0576-5
- Pico F, Iba ez J, Centeno TA, Pecharroman C, Rojas RM, Amarilla JM, Rojo JM (2006) *Electrochim Acta* 51:4693. doi:10.1016/j.electacta.2005.12.040
- Sugimoto W, Iwata H, Yokoshima K, Murakami Y, Takasu Y (2005) *J Phys Chem B* 109:7330. doi:10.1021/jp044252o